

# Design Patents in the U.S. and Japan: Leveraging the Differences in Laws to Maximize Protection

Fitch, Even, Tabin & Flannery LLP will present a free webinar, "Design Patents in the U.S. and Japan: Leveraging the Differences in Laws to Maximize Protection," featuring Fitch Even partner Calista J. Mitchell and Konishi & Nakamura partner Tomohiro Nakamura.

The webinar will take place on Thursday, May 20, 2021, at 9:00 am PDT / 10:00 am MDT / 11:00 am CDT / 12 noon EDT.

Design patent laws can differ significantly from one country to another. A lack of understanding of these differences can result in not obtaining the broadest patent protection possible. This webinar will provide an overview of the basics of the design patent laws in the U.S. and Japan and then examine how applicants can take advantage of unique opportunities each country's laws have to offer.

In particular, the presenters will address the following topics:

- Patentability requirements for designs in the U.S. and in Japan
- Best practices for preparing a priority application in one country that is suitable for filing in the other
- Unique filing or prosecution strategies permitted in each country
- Enforcement considerations
- Highlights of Japan's New Design Act of 2020 and the implications and opportunities for applicants filing secondary applications in Japan

CLE credit has been approved for California and Illinois and is pending for Nebraska. Other states may also award CLE credit upon attendee request.

**Register for the event.**

Following the live event, a recording of the webinar will be available to view for one year at [www.fitcheven.com](http://www.fitcheven.com).